

A MECHANISM FOR INTER-FAB MASK PROCESS MANAGEMENT

ABSTRACT

[0052] A software mechanism is provided for inter-fab mask process management. The mechanism is used for tracking and managing a plurality of lithographic masks through a semiconductor manufacturing environment. A virtual fab is established with a plurality of entities, each entity associated with an internal process to a semiconductor fab or an external process to the semiconductor fab. A state diagram tracks the plurality of lithographic masks through the plurality of entities of the virtual fab. Each of the plurality of lithographic masks is placed at a pre-determined state of the state diagram and a future location for each of the masks in the virtual fab is determined via the state diagram.